

ABSTRACT

Method for fabricating a structure in the form of a plate, and structure in the form of a plate, in particular formed from silicon, comprising at least one substrate (2), a superstrate (3) 5 and at least one intermediate layer (4) interposed between the substrate and the superstrate, in which the intermediate layer (4) comprises at least one base material having distributed therein atoms or molecules termed extrinsic atoms or molecules which differ from the atoms or molecules of the base material, and in which a heat treatment is applied to said plate so that, in the temperature range of said heat treatment, the intermediate layer (4) is plastically deformable 10 and the presence of the selected extrinsic atoms or molecules in the selected base material causes the irreversible formation of micro-bubbles or micro-cavities (7) in the intermediate layer.